

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of Docket No: Q84137  
Shinichi ISHIBASHI, et al. Allowed: February 7, 2008  
Appln. No.: 10/510,916 Group Art Unit: 1795  
Confirmation No.: 7320 Examiner: Stephen D. Rosasco  
Filed: October 12, 2004

For: REFLECTIVE MASK BLANK, REFLECTIVE MASK AND METHODS OF  
PRODUCING THE MASK BLANK AND THE MASK

**INFORMATION DISCLOSURE STATEMENT**  
**UNDER 37 C.F.R. §§ 1.97 and 1.98**

**MAIL STOP ISSUE FEE**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby  
notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached  
PTO/SB/08 A & B (modified) form and/or listed herein and which the Examiner may deem  
material to patentability of the claims of the above-identified application.

One copy of each of the listed documents is submitted herewith, along with a copy of the  
corresponding Communication from a Foreign Patent Office, except for the following: U.S.  
patents and/or U.S. patent publications; and co-pending non-provisional U.S. applications filed  
after June 30, 2003.

The present Information Disclosure Statement is being filed after either a Final Office  
Action, Notice of Allowance, or an action that otherwise closes prosecution in the application

(whichever is earlier), but before payment of the Issue Fee, and therefore the fee of \$180.00 under 37 C.F.R. § 1.17(p) is submitted herewith through the EFS Deposit Account, with a Statement Under 37 C.F.R. § 1.97(e) and a copy of a Communication from a foreign patent office dated January 16, 2008 in a counterpart application citing such documents.

JP 2001-237174 was previously cited in the Information Disclosure Statement filed June 9, 2005. M. Takahashi., et al, Smooth Low-stress sputtered tantalum and tantalum alloy films for the absorber material of reflective-type EUVL" was previously cited in the Information Disclosure Statement filed December 5, 2007.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this paper is attached.

Respectfully submitted,

*/Alan J. Kasper/*

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SUGHRUE MION, PLLC  
Telephone: (202) 293-7060  
Facsimile: (202) 293-7860

Alan J. Kasper  
Registration No. 25,426

WASHINGTON OFFICE  
**23373**  
CUSTOMER NUMBER

Date: April 18, 2008

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**STATEMENT UNDER 37 C.F.R. § 1.97(e)**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

The undersigned hereby states, upon information and belief:

That each item of information contained in the Information Disclosure Statement filed concurrently herewith was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of said Information Disclosure Statement.

Respectfully submitted,

*/Alan J. Kasper/*

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